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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

John E. Lang

Application No. 09/274,194

Filed: March 22, 1999

For: METHOD OF REMOVING PHOTORESIST
MATERIAL WITH DYMETHYL SULFOXIDE

Group: 1765

Examiner: C. Brown

Attny Docket No. 60265-308301

Date: February 23, 2001

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner of Patents and Trademarks, Washington, DC 20231 on February 23, 2001.

Signed: _____

Lori Cox

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AMENDMENT A

Under 37 C.F.R. §1.111

Commissioner for Patents
Washington, DC 20231

Dear Sir:

In response to the Office Action dated October 24, 2000, the period for response extending until January 24, 2000, please enter the following amendments and consider the following remarks. The required fee for a one-month extension of time is submitted herewith.

In the claims:

Please amend the claims as follows:

1. (Amended) A method of removing photoresist material from a semiconductor substrate, comprising:

providing a semiconductor substrate having a layer comprised of a low dielectric constant material disposed thereover and a layer comprised of photoresist material disposed over said layer comprised of said low dielectric constant material; [and]

Attorney Docket: 60265-308301 (LAM1P083A)